Attorney's Docket No.: 09464-025001

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Budong You et al.

Art Unit : 2818

Serial No.: 10/713,749

Examiner: Dung Anh Le

Filed

: November 13, 2003

Conf. No.: 1619

Title

: A LATERAL DOUBLE-DIFFUSED MOSFET

MAIL STOP RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicants request consideration of the references listed on the attached PTO-1449 form. Under 37 C.F.R. § 1.98 (a)(2)(ii), only copies of foreign patent documents and/or non-patent literature are enclosed. Copies of any listed U.S. patents or U.S. patent application publications can be provided upon request.

This filing is being made with the filing of a Request for Continued Examination. No fee is required.

Respectfully submitted,

Date: 12/29/06

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Substitute Form PTO-1449 U.S. Department of Commerce (Modified) Patent and Trademark Office		Attorney's Docket No. 09464-025001	Application No. 10/713,749	
•••••	losure Statement plicant	Applicant Budong You et al.		
(Use several sheets if necessary)		Filing Date	Group Art Unit	
(37 CER \$1.98(b))		November 13, 2003	2818	

Examiner	Desig.	Document	Publication	ent Documents			Filing Date
Initial	Desig.	Number	Date	Patentee	Class	Subclass	If Appropriate
	AA	4,769,686	09/1988	Horiuchi, et al.			
	AB	5,275,961	01/1994	Smayling, et al.			
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	AP	7,074,659	07/2006	Zuniga, et al.		* "	
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	AS	2002/0030238	03/2002	Nakamura, et al.			
	AT	2002/0079514	06/2002	Hower, et al.			
	AU	2002/0089790	07/2002	Stoebe, et al.			
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	AY	2005/0106791	05/2005	You, et al.			
	AZ	2005/0106825	05/2005	You, et al.			

Examiner Signature	Date Considered
LAGITIMOT DIGITATION	
EVAMINED: Initials citation considered. Drawline through citation if no	t in conformance and not considered. Include copy of this form with

next communication to applicant.

Substitute Form PTO-1449 (Modified)			Application No. 10/713,749	
(Use several sheets if necessary)		Applicant Budong You et al.		
		Filing Date November 13, 2003	Group Art Unit 2818	

AAA	7,074,659	07/2006	Zuniga, et al.	
ABB	7,038,274	05/2006	Budong You, et al.	
ACC	11/232,516		Budong You, et al.	9/2005
ADD	2006/0205168	09/2006	Zuniga, et al.	

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner	Desig.	Document	Publication	Country or			Trans	lation
Initial	ID D	Number	Date	Patent Office	Class	Subclass	Yes	No
	AEE							<u></u>
	AFF							

Other Documents (include Author, Title, Date, and Place of Publication)					
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Initial	ID	Document			
	AGG	S. Wolf, "Silicon Processing for the VLSI Era", Volume 2 – Process Ingtegration, page 662; Lattice Press, Sunset Beach, California 90742 (ISBN: 0-961672-4-5) (1990)			
	АНН	S. Wolf, "Silicon Processign in the VLSI Era", Volume 3 – The Submicro MOSFET, pages 591-593, Lattice Press, Sunset Beach, California (1995)			
	AII	Webster's Collegiate Dictionary, 10 th Edition, Springfield, Massachusetts (1999), page 222.			
	AJJ				

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if no	t in conformance and not considered. Include copy of this form with

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